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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/576,321	04/19/2006	Kazunari Kurita	12054-0059	9391
22902 CLARK & BRO	7590 02/18/201 ODY	0	EXAMINER	
1090 VERMONT AVENUE, NW			KUNEMUND, ROBERT M	
SUITE 250 WASHINGTON, DC 20005			ART UNIT	PAPER NUMBER
			1792	
			MAIL DATE	DELIVERY MODE
			02/18/2010	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)				
Office Action Comments	10/576,321	KURITA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Robert M. Kunemund	1792				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).						
Status						
1) Responsive to communication(s) filed on 21	October 2009					
·	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
•	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
closed in accordance with the practice under Ex parte Quayle, 1933 C.D. 11, 433 C.G. 213.						
Disposition of Claims						
4)⊠ Claim(s) <u>1-8</u> is/are pending in the application	Ⅺ Claim(s) <i>1-8</i> is/are pending in the application.					
4a) Of the above claim(s) is/are withdr	4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-8</u> is/are rejected.						
7) Claim(s) is/are objected to.						
Application Papers						
9) The specification is objected to by the Examiner.						
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) 4) Interview Summary (PTO-413) Paper No(s)/Mail Date 5) Notice of Informal Patent Application						
Paper No(s)/Mail Date 6) Other:						

DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 1 to 5 are rejected under 35 U.S.C. 103(a) as being unpatentable over Abe (EP 1,087,041) in view of IKari (JP 2000-344,598) and Tobe (2004/0102056). The Abe reference teaches a method of producing a high-resistance silicon wafer having a resistivity of 100 cm or more, oxygen concentration of 14x1017 atoms/cm³ or more remaining oxygen concentration of 12x10⁻⁷ atoms/cm³ or less by performing heat treatment performed at 700-900°C for 5 hours or more, a heat treatment performed at 950-1050°C for 10 hours or more, a heat treatment performed at 1100-1250°C for 1-5 hours, and a density of a grown-in defect of lx103/cm ³. The difference between the

instant claims and the prior art is the carbon concentration and third annealing step. However, the Ikari reference teaches the claimed carbon concentrations in silicon wafer grown by czochralski, Note translted abs. The Tobe reference teaches a third annealing step after the high temperature annealing, note page 1. It would have been obvious to one of ordinary skill at the time of the invention to modify the Abe reference by the teachings of the Ikari and Tobe references to have a set carbon concentration and third annealing in order to create the desired properties in the final silicon wafer.

Claims 6 to 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Abe (EP 1,087,041) in view of IKari (JP 2000-344,598) and Tobe (2004/0102056).

The Abe, Ikari and Tobe references are relied on for the same reasons as stated, supra, and differ from the instant claims in the materials deposited onto the silicon wafers. However, in the absence of unexpected results, it would have been obvious to one of ordinary skill in the art to determine through routine experimentations the optimum, operable after growth in the combined prior art in order to grow a specific device.

Response to Applicants Arguments

Applicant's arguments filed October 21, 2009 have been fully considered but they are not persuasive.

Applicants' argument concerning the Tobe reference is noted. However, the reference does teach the claimed cooling step and rates. The reference further teaches as do other references of record that different steps, temperatures and rates do

materially effect the silicon wafer that is being treated. This is well known to one of ordinary skill in the art. Therefore, it is well within the skill and obivous to modify the primary reference by the teachings of the Tobe and use a different cooling process in order to change the wafer.

Applicants' argument concerning the Abe reference has been considered and not deemed persuasive. The Abe reference does in fact teach the claimed two step heating in the order claimed, note example 4. The reference is properly applied against the claims.

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Robert M. Kunemund whose telephone number is 571-272-1464. The examiner can normally be reached on 8 hours.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Kornakov can be reached on 571-272-1303. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Robert M Kunemund Primary Examiner Art Unit 1792

RMK

/Robert M Kunemund/ Primary Examiner, Art Unit 1792